

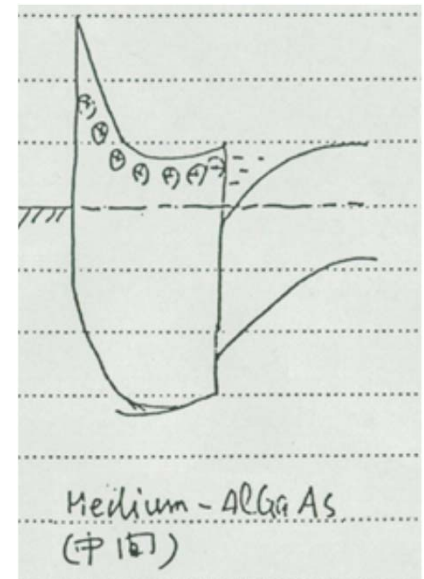
# The High-Electron Mobility Transistor at 30: Impressive Accomplishments and Exciting Prospects

J. A. del Alamo

Microsystems Technology Laboratories  
MIT

International Conference on  
Compound Semiconductor Manufacturing Technology

May 16-19, 2011



# Outline

- Introduction
- HEMT electronics
- Modulation-doped structures in physics
- Future prospects

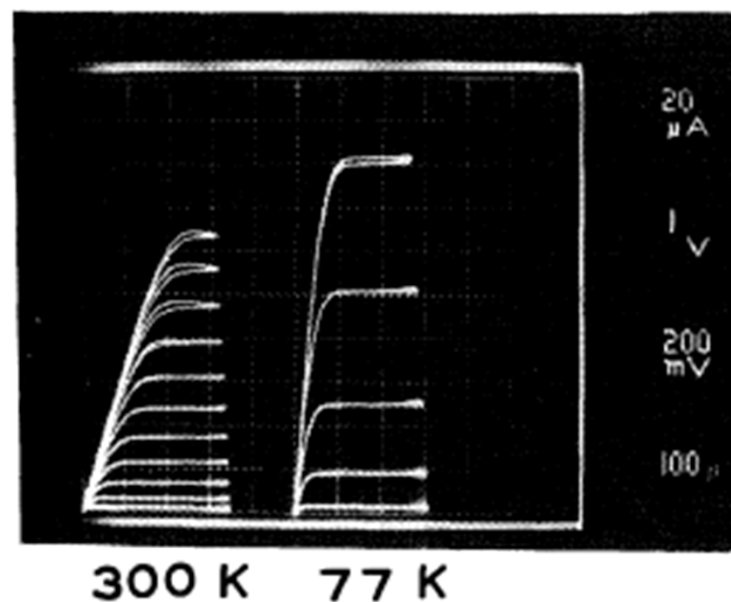
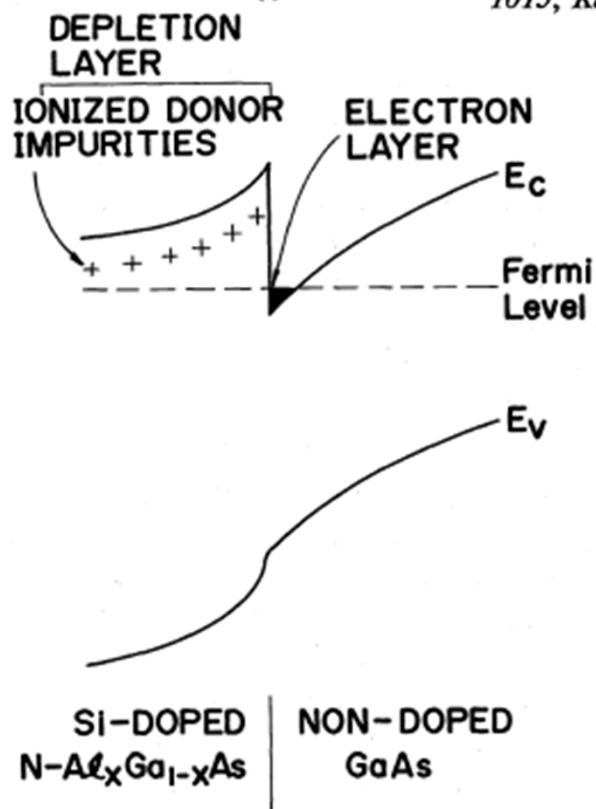
# The High Electron Mobility Transistor

## A New Field-Effect Transistor with Selectively Doped GaAs/n-Al<sub>x</sub>Ga<sub>1-x</sub>As Heterojunctions

Takashi MIMURA, Satoshi HIYAMIZU, Toshio FUJII  
and Kazuo NANBU

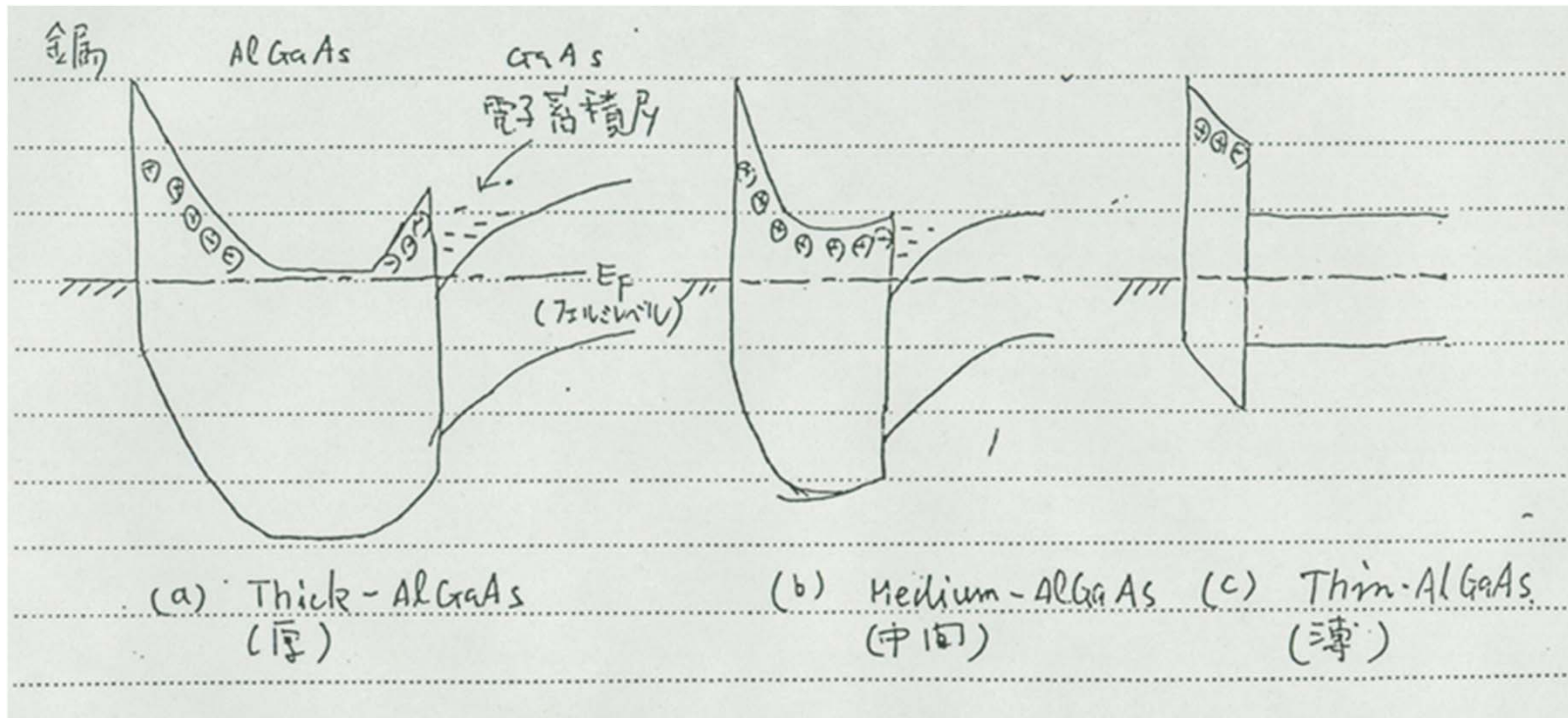
*Fujitsu Laboratories Ltd.,  
1015, Kamikodanaka, Nakahara-ku, Kawasaki 211*

(Received March 24, 1980)



Mimura, JJAPL 1980

# Energy band diagrams in Mimura's patent application (Aug. 16, 1979)

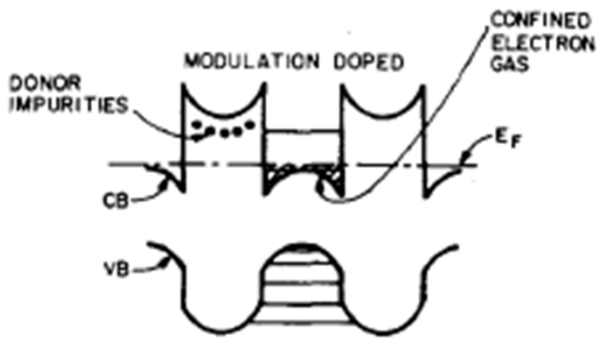


Courtesy of Takashi Mimura (Fujitsu)

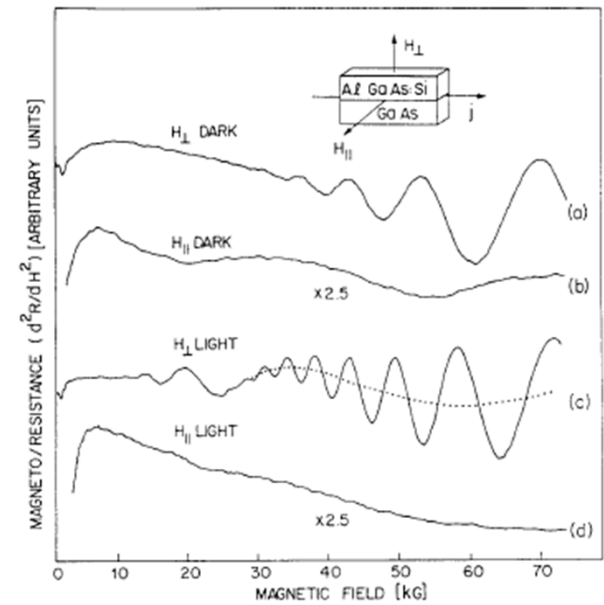
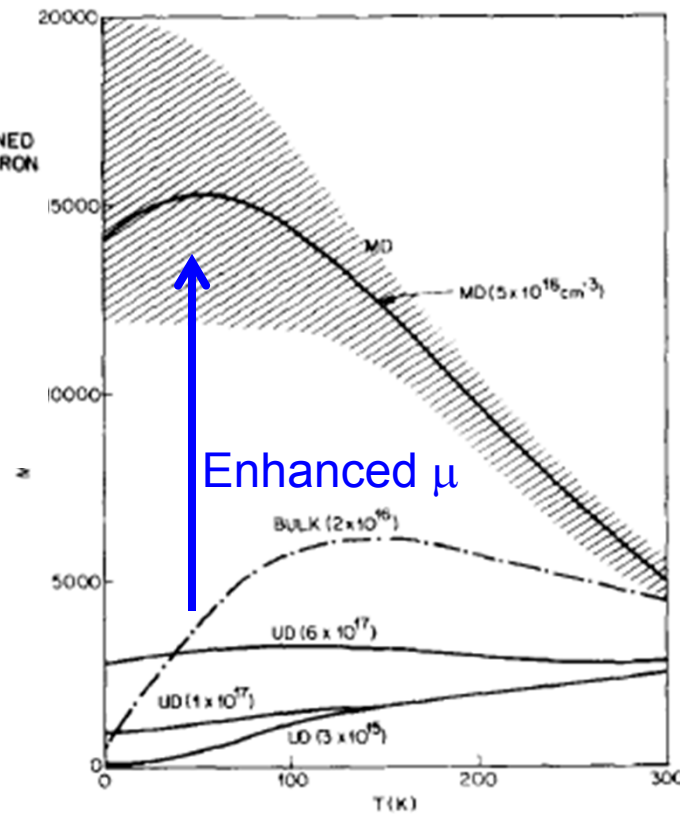


# Modulation doping

- High electron mobility in modulation-doped AlGaAs/GaAs heterostructures
- 2 DEG at AlGaAs/GaAs interface

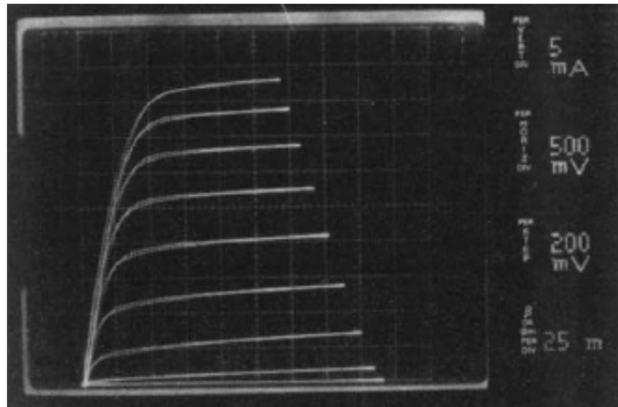


Dingle, APL 1978



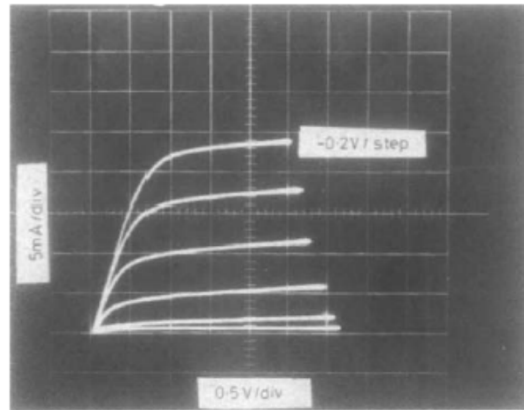
Störmer, Solid St  
Comm 1979

# HEMT by other name...



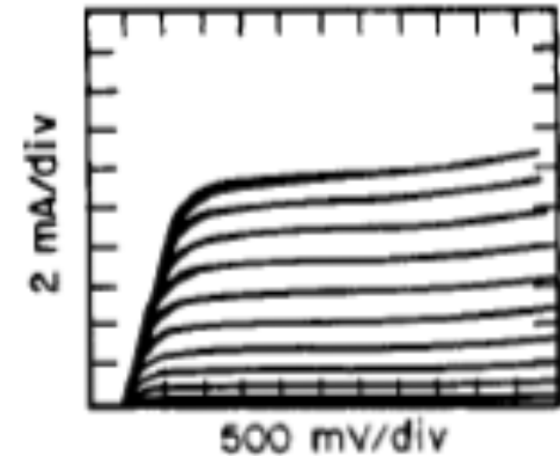
Thomson-CSF:  
Two-Dimensional Electron  
Gas FET (TEGFET)

Laviron, EL 1981



U. Illinois:  
Modulation-Doped FET  
(MODFET)

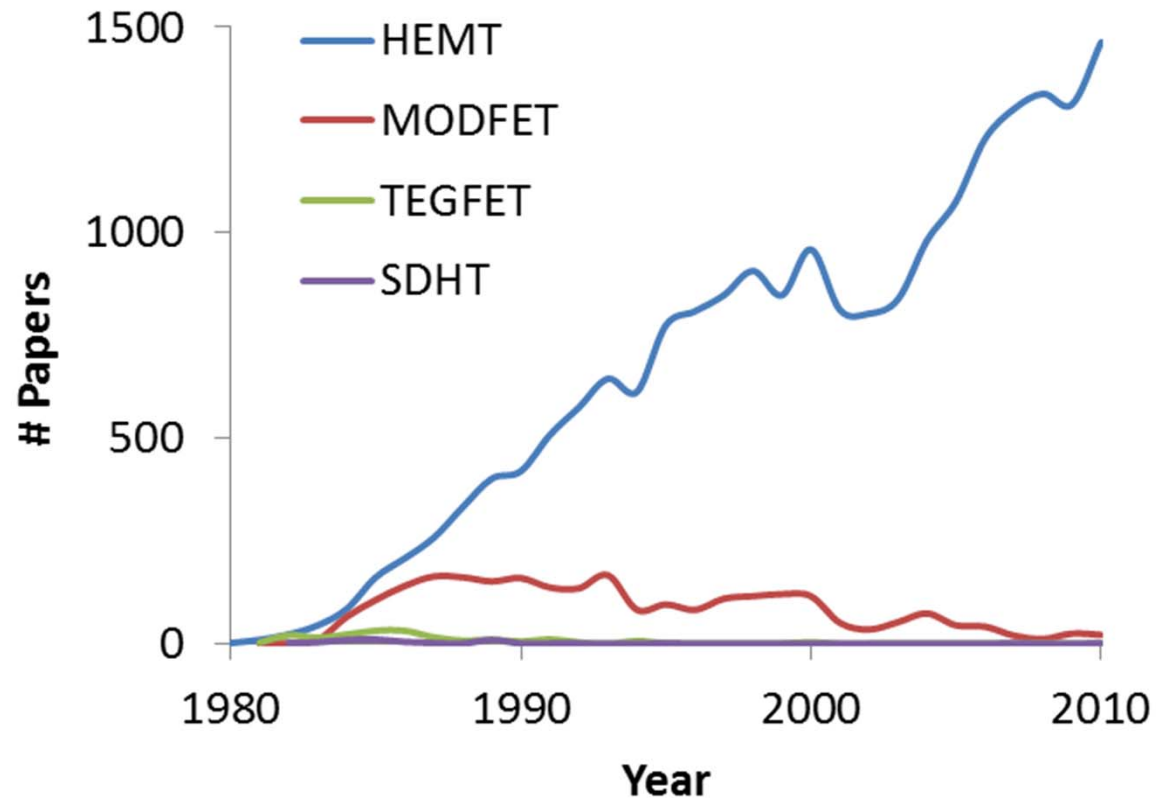
Su, EL 1982



Bell Labs.:  
Selectively-Doped  
Heterojunction Transistor  
(SDHT)

DiLorenzo, IEDM 1982

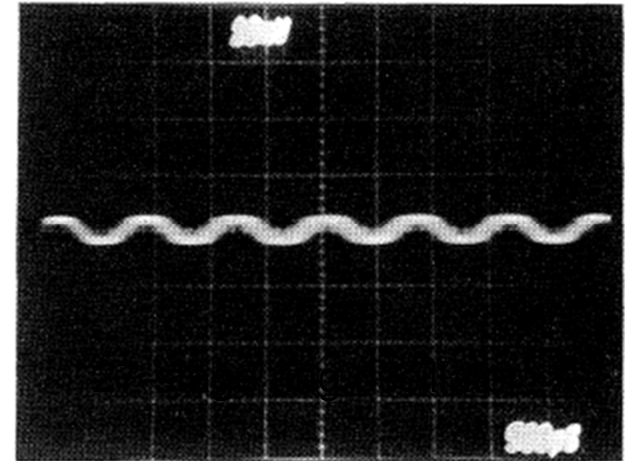
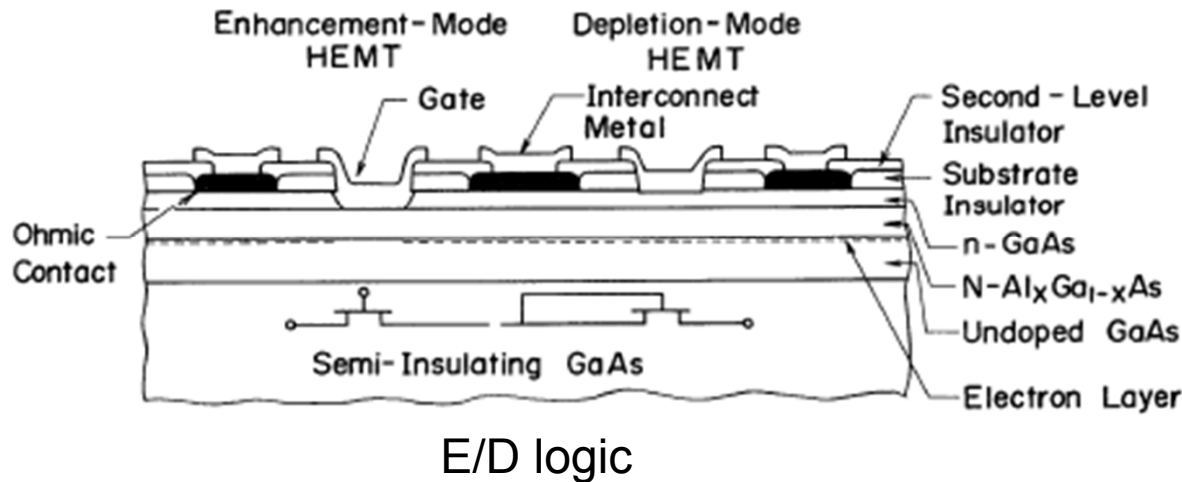
## And the winner is...



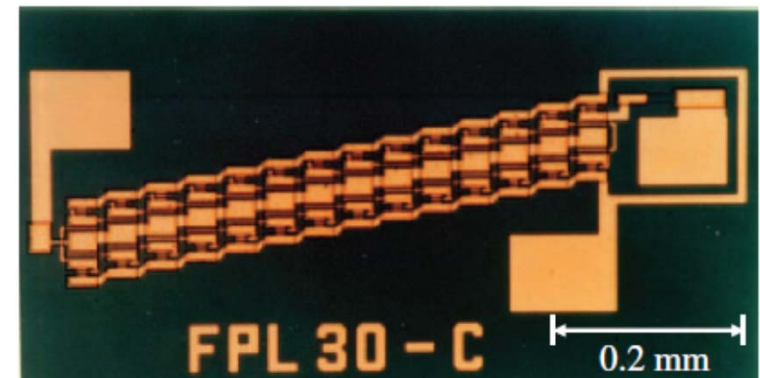
# papers in Compendex and Inspec databases with keyword in title, abstract or indexing terms

Data courtesy of Angie Locknar (MIT Libraries)

# First HEMT IC



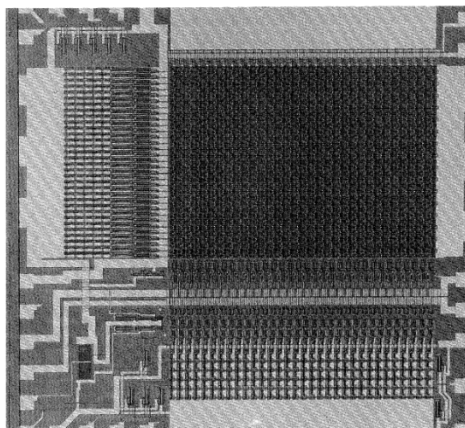
“The switching delay of 17.1 ps is the lowest of all the semiconductor logic technologies reported thus far.”



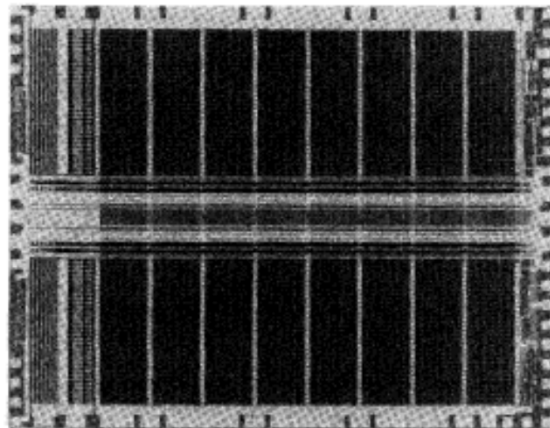
Mimura, JJAPL 1981

“HEMT technology is presenting new possibilities for high-speed low-power very-large-scale-integration.”

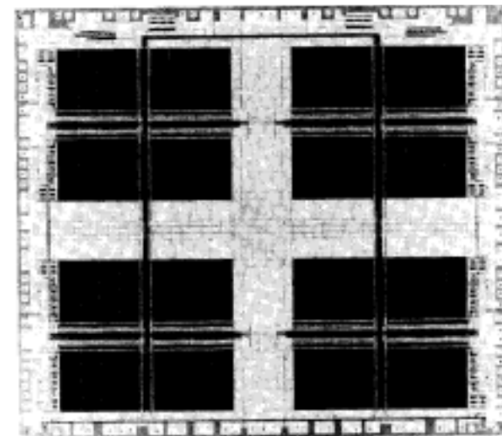
# HEMT ICs ride Moore's Law



1 Kb SRAM



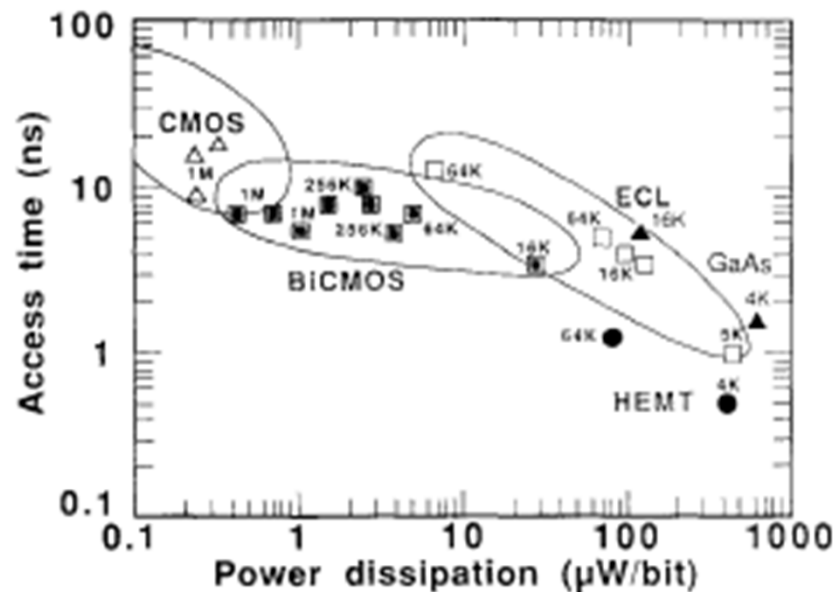
16 Kb SRAM



64 Kb SRAM

- 1984: 1 Kb SRAM (7,244 HEMTs, 8.7 mm<sup>2</sup>)
- 1984: 4 Kb SRAM (26,864 HEMTs, 21 mm<sup>2</sup>)
- 1987: 16 Kb SRAM (107,519 HEMTs, 24 mm<sup>2</sup>)
- 1991: 64 Kb SRAM (>462,000 HEMTs, 48 mm<sup>2</sup>)

Watanabe, TED 1987    Abe, JSSC 1991  
 Suzuki, JSSC 1991    Abe, JVST1987



# First HEMT LNA

20 GHz 4-stage HEMT LNA (1983)

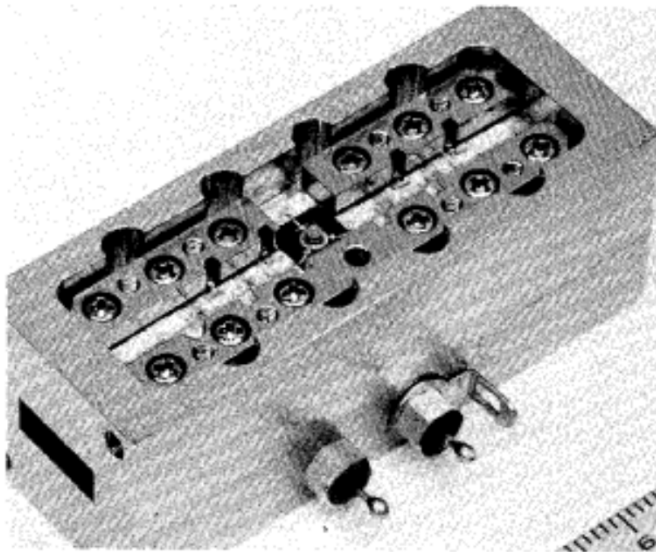
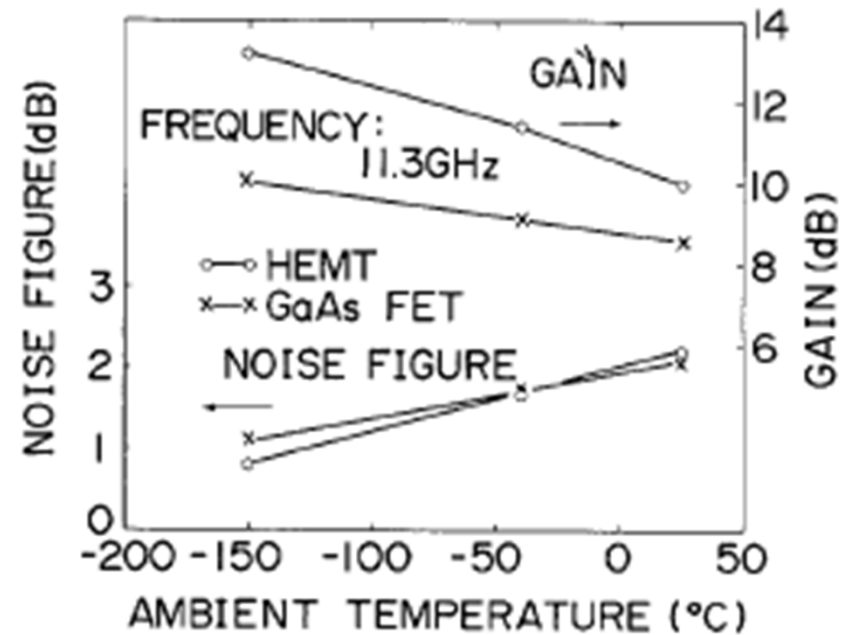


FIGURE 4—A 20GHz 4-stage HEMT amplifier.



Niori, ISSCC 1983

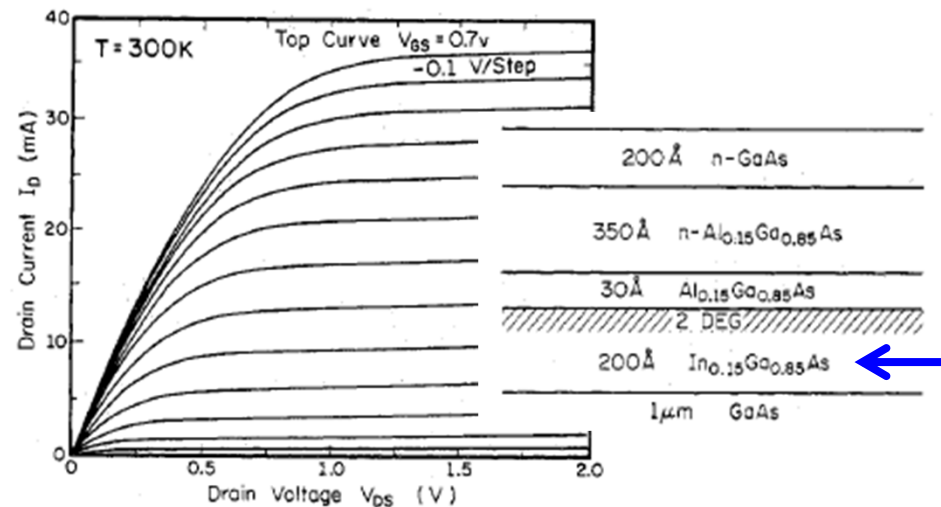
Great improvement in noise characteristics as  $T \downarrow$





# Delta-doped pseudomorphic HEMT

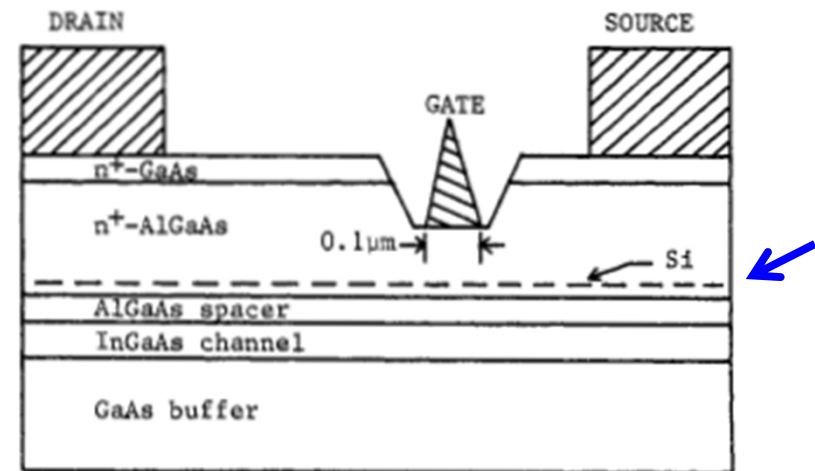
## Pseudomorphic HEMT



Ketterson, EDL 1985

- Motivation: lower  $x$  in  $Al_xGa_{1-x}As$  to avoid carrier freeze-out
- Enhanced transport in InGaAs
- Large  $\Delta E_c \rightarrow$  enhanced current

## Delta doping



Chao, IEDM 1987

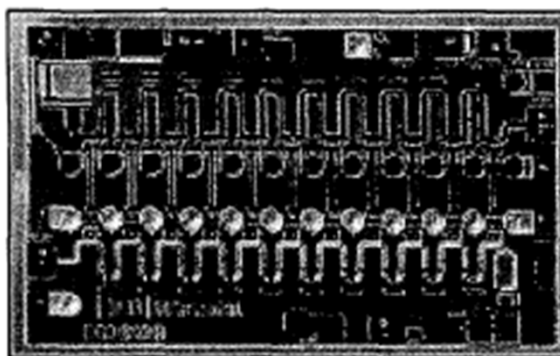
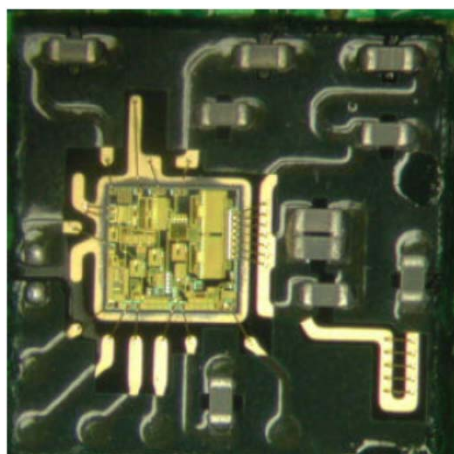
- Enabled barrier thickness scaling  $\rightarrow$  improved transconductance and scalability
- Enhancement of breakdown voltage



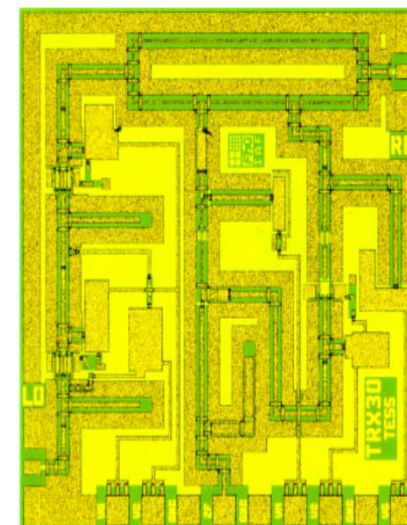
# PHEMT ICs

Saturday, February 26, 2011  
**TriQuint and Skyworks Power iPhone 5**

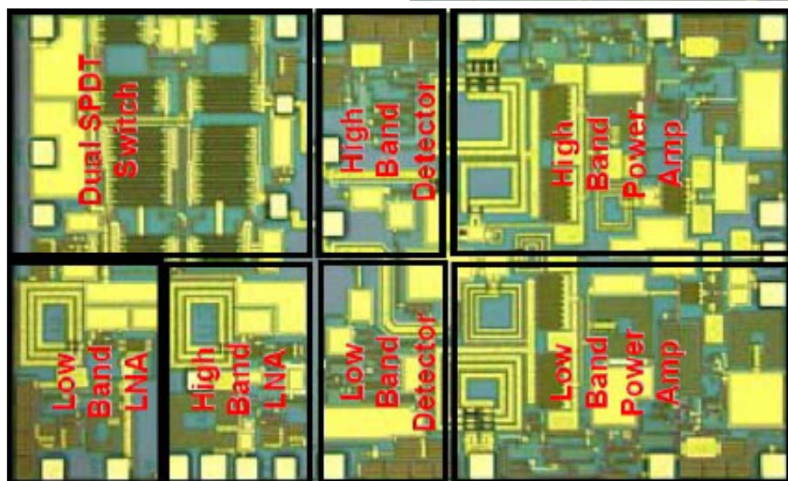
UMTS-LTE PA module  
 Chow, MTT-S 2008



40 Gb/s modulator driver  
 Carroll, MTT-S 2002

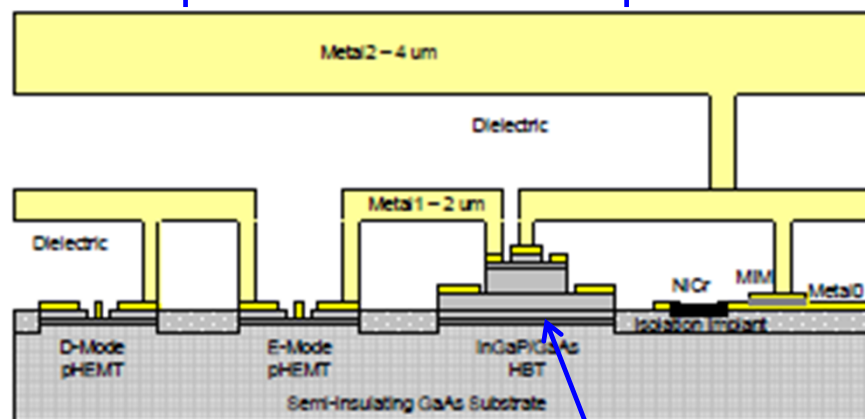


77 GHz transceiver  
 Tessmann, GaAs IC  
 1999



Single-chip WLAN MMIC, Morkner, RFIC 2007

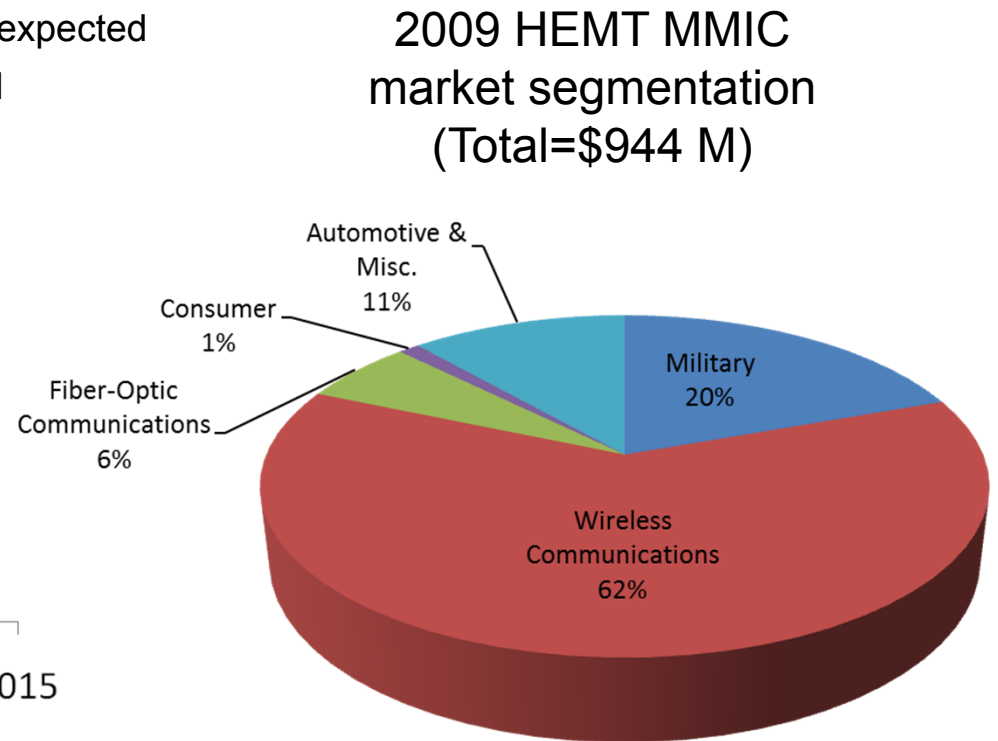
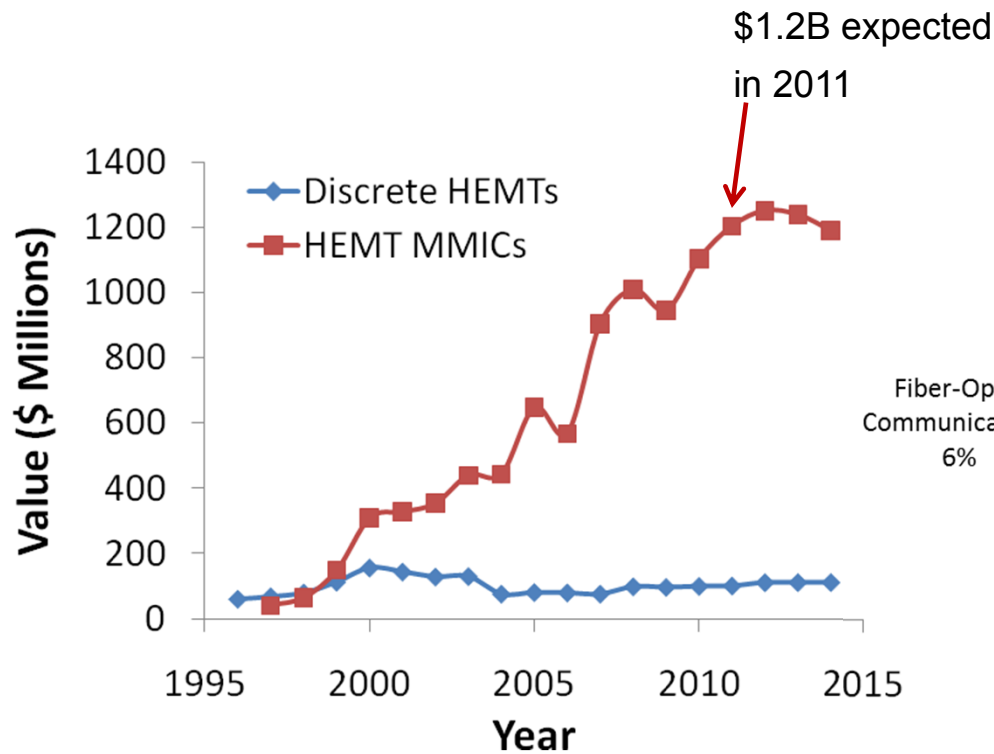
## Bipolar/E-D PHEMT process



Henderson, Mantech 2007

Single MOCVD growth 13

# HEMT markets

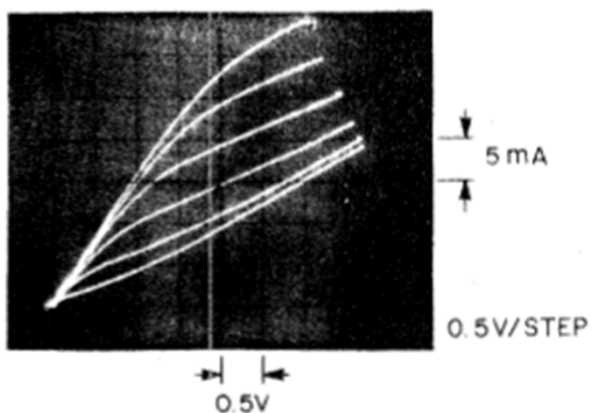
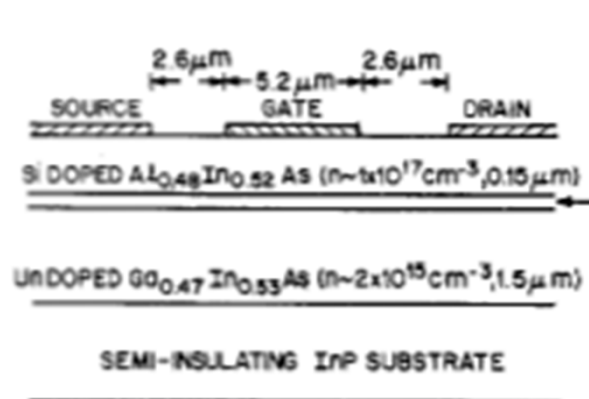


- Biggest market: wireless communications
- Biggest applications: cell phone handsets, WLAN, base stations and CATV

Data courtesy of Eric Higham (Strategy Analytics)

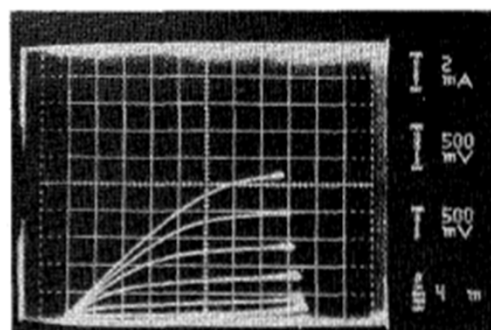
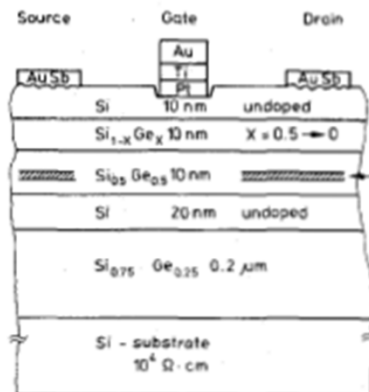
# HEMTs in other material systems

## InAlAs/InGaAs on InP



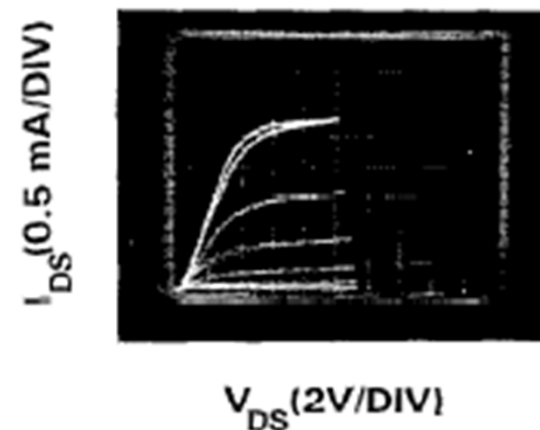
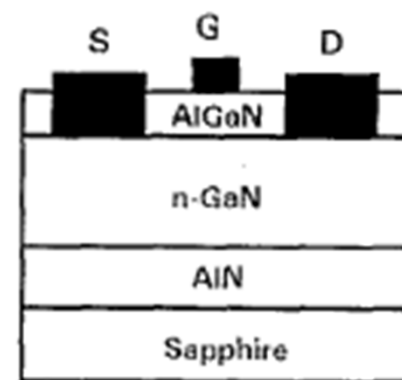
Chen, EDL 1982

## SiGe/Si



Daembkes, TED 1986

## AlGaN/GaN

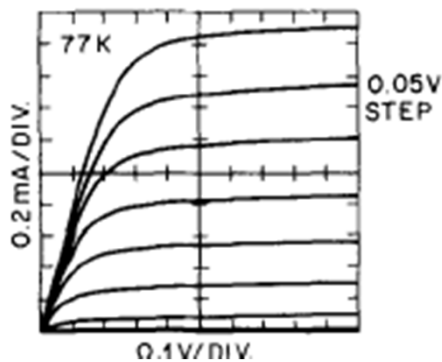
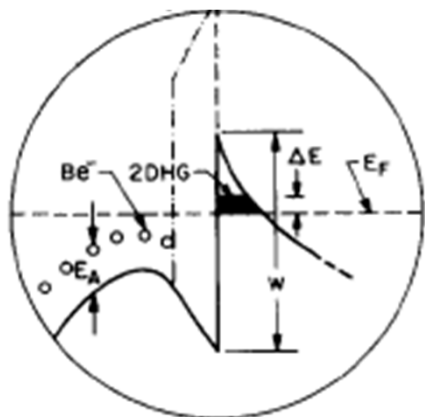


Khan, APL 1993

Also: AlSb/InAs, AlInSb/InSb, etc

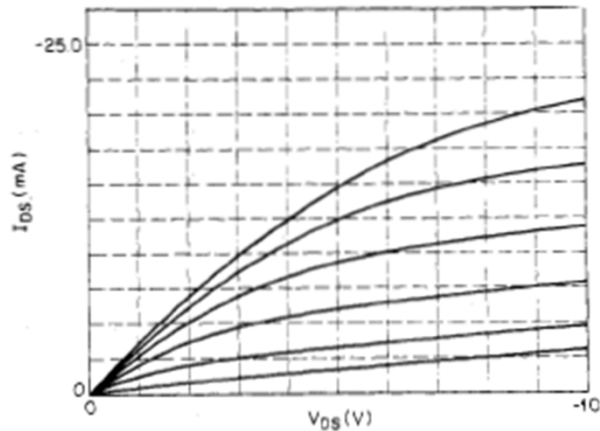
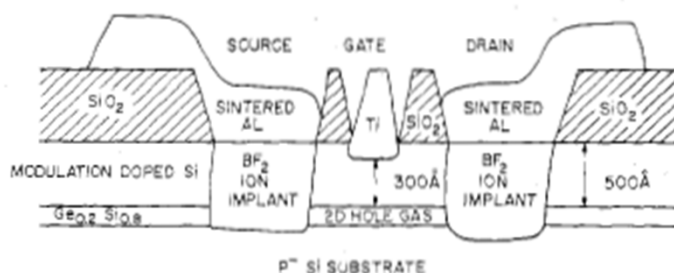
# High *Hole* Mobility Transistors

AlGaAs/GaAs



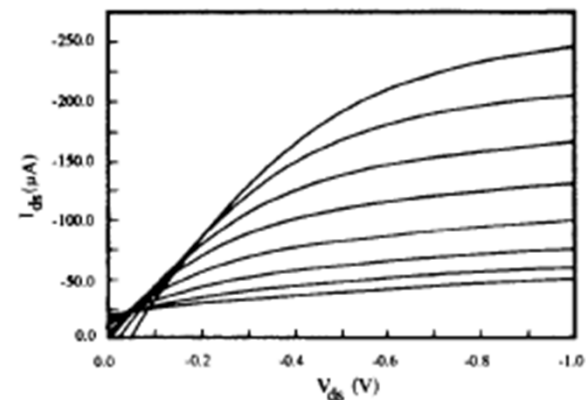
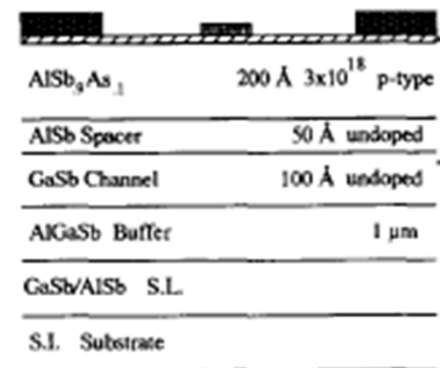
Störmer, APL 1984

Si/SiGe



Pearsall, EDL 1986

AlSbAs/GaSb



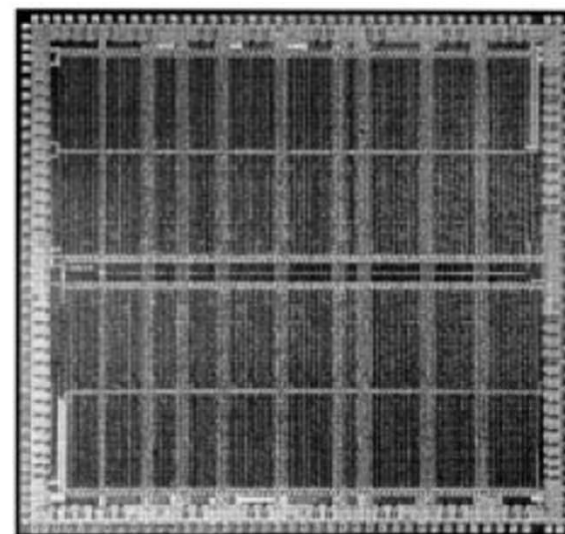
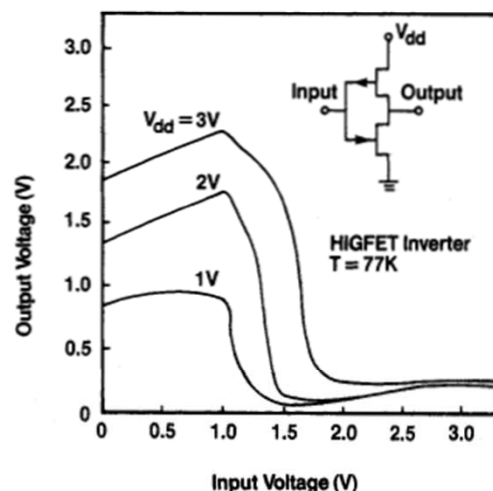
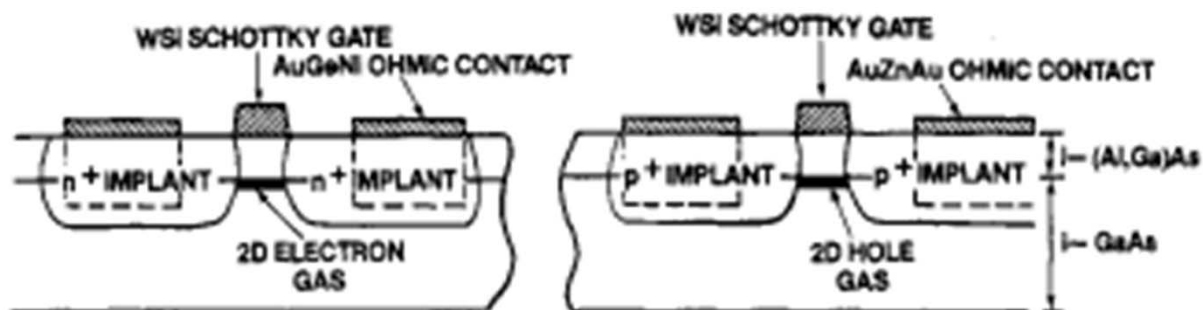
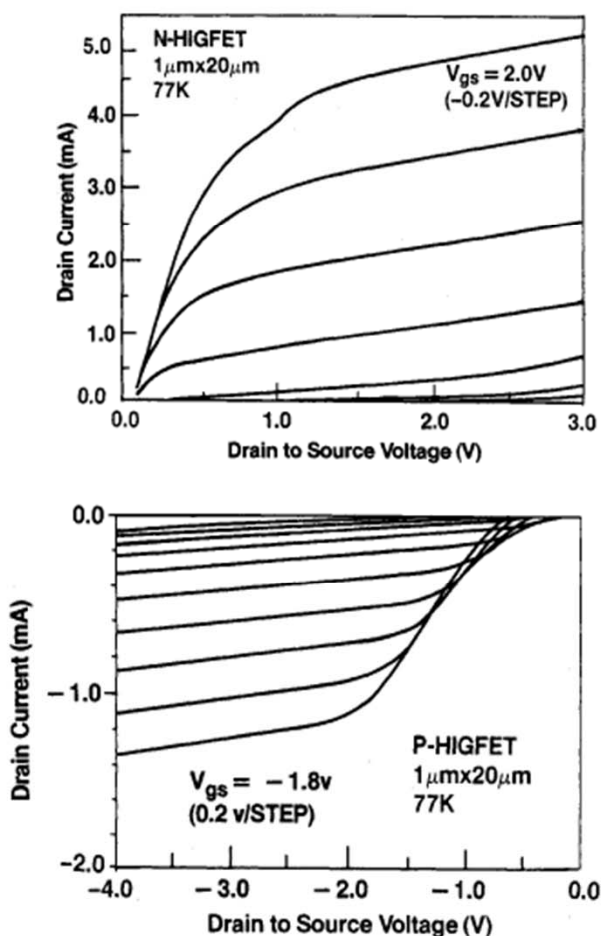
Luo, EDL 1990

Also: AlGaAs/InGaAs, InAlAs/InGaAs, AlGaSb/InGaSb, InGaN/GaN, etc



# Complementary HEMT/HHMT ICs

## AlGaAs/GaAs system



Cirillo, IEDM 1985

171,000 transistor 16-channel signal distribution system

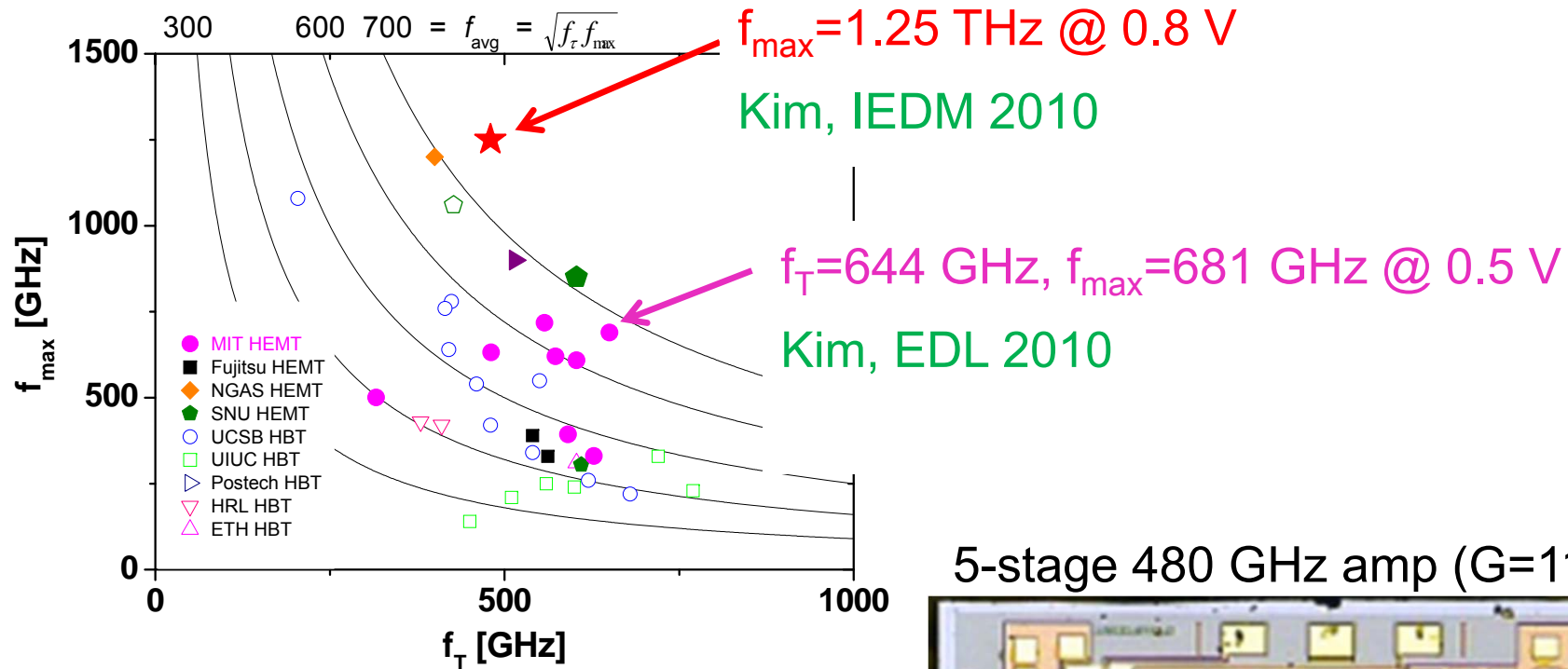
Also: InAlAs/InGaAs system

Brown, Trans VLSI Syst 1998

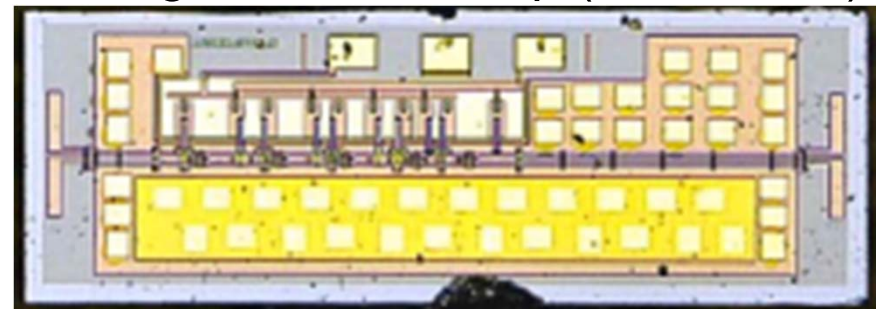
# InAlAs/InGaAs HEMTs on InP

Uniqueness: very high mobility and velocity

→ record frequency response at very low voltage



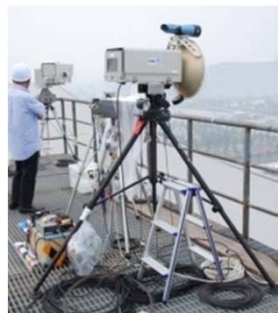
5-stage 480 GHz amp (G=11.7 dB)



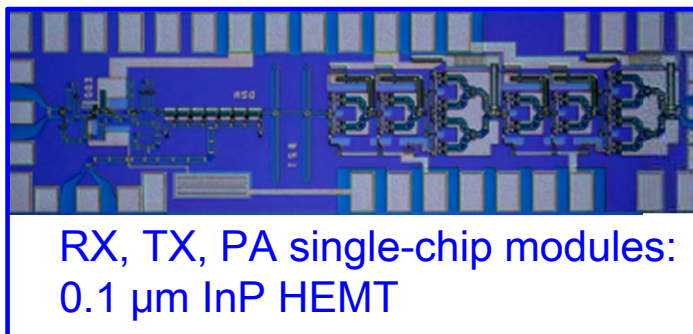
Deal, MWCL 2010

# InAlAs/InGaAs HEMT mmw ICs

120-GHz-band link at Beijing Olympics  
(10 Gb/s over 1 km)



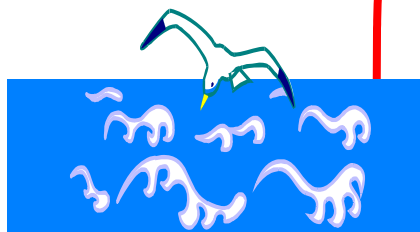
JC Fuji TV booth



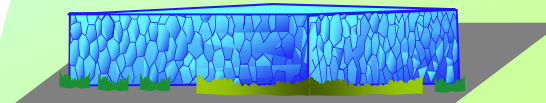
RX, TX, PA single-chip modules:  
0.1  $\mu\text{m}$  InP HEMT



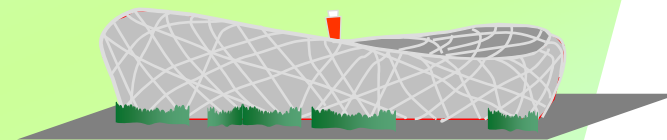
Live-uncompressed HD video



TV station  
(Japan)



Water Cube

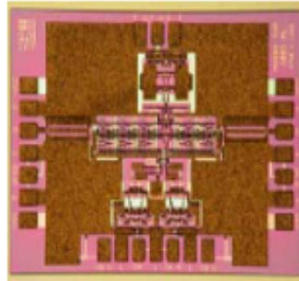
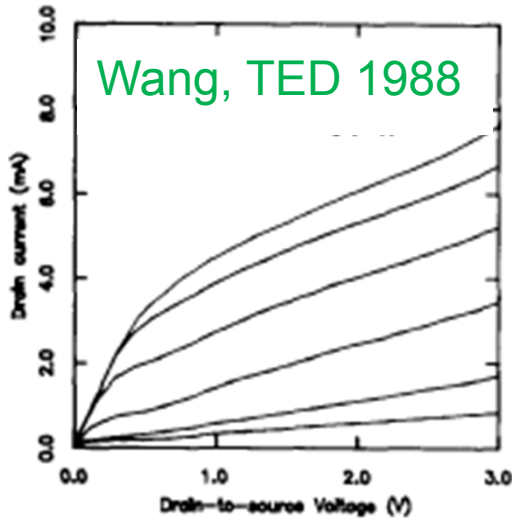


National Stadium

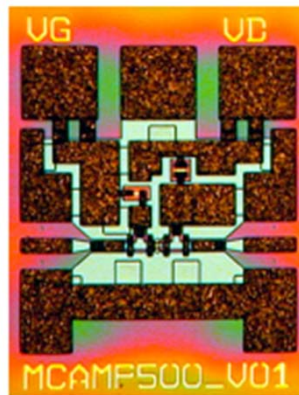
Courtesy of Akihiko Hirata (NTT)

Hirata, TMTT 2009

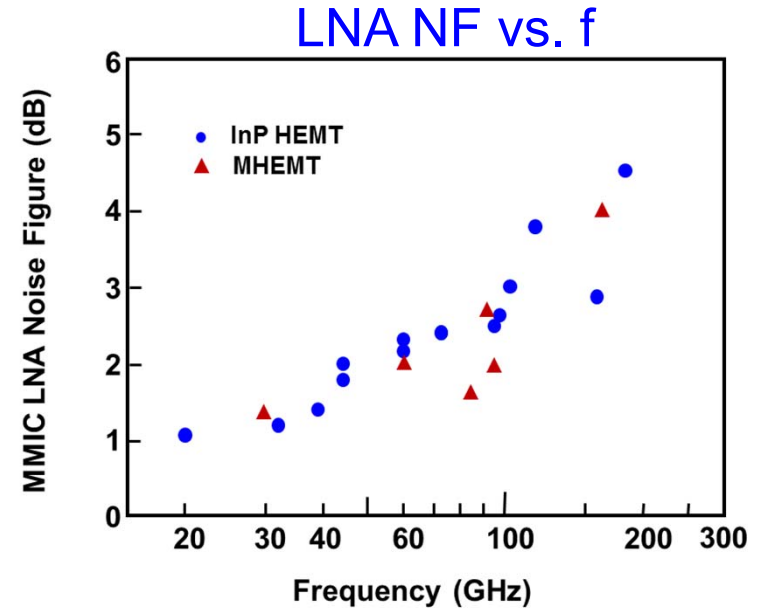
# InAlAs/InGaAs Metamorphic HEMTs *on GaAs*



80 Gb/s multiplexer IC



Single-stage 500 GHz LNA (G=3.3 dB)

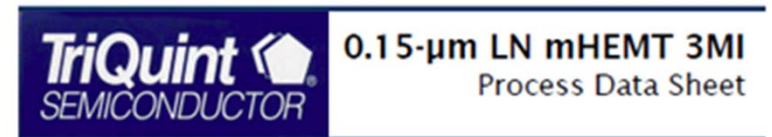


Wurfl, GAAS 2004

Tessmann, CSIC 2010

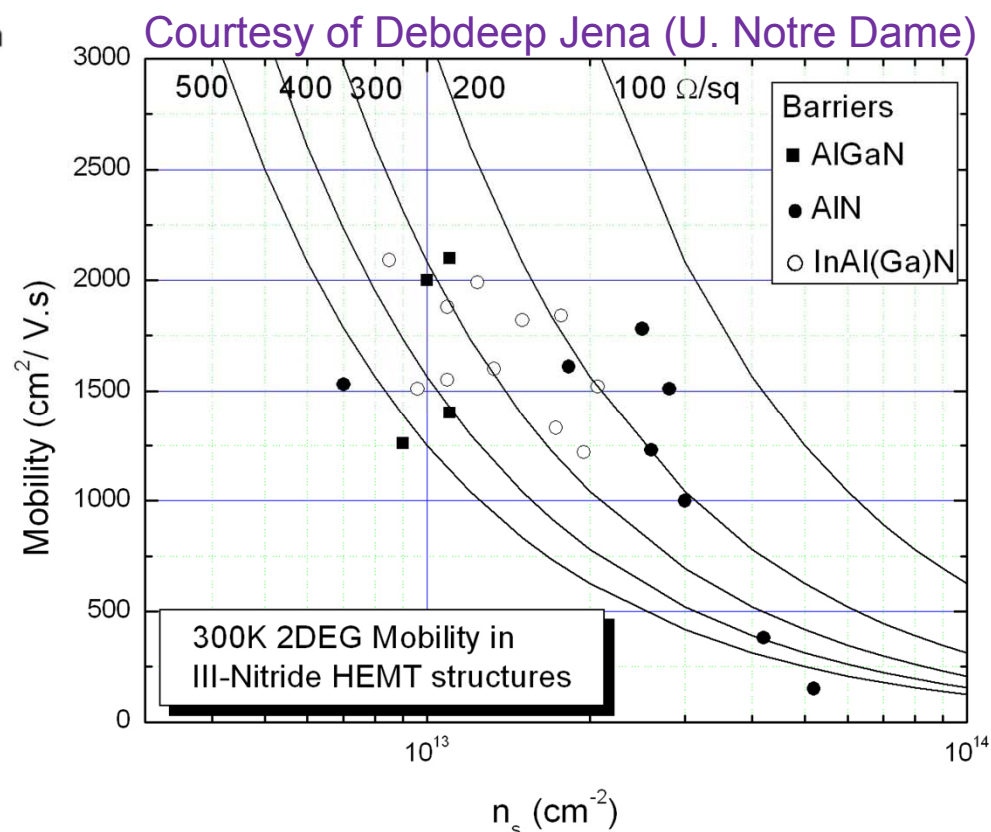
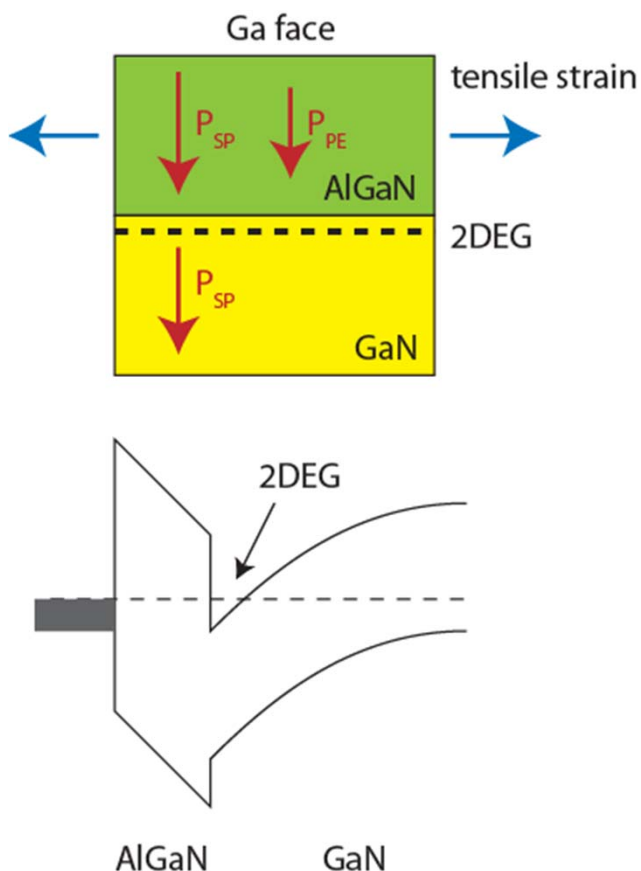
- Comparable performance to InP substrate
- Improved manufacturability
- Lower cost
- Well established packaging technology

LNA data courtesy of Phillip Smith (BAE Systems)





# Polarization doping in Nitrides

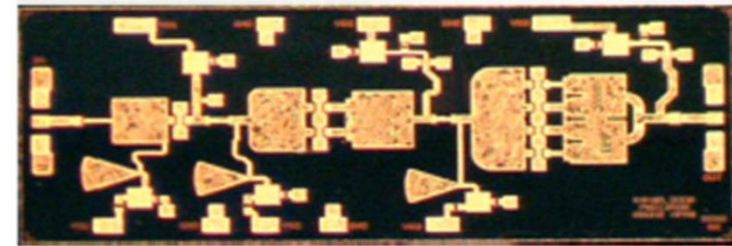
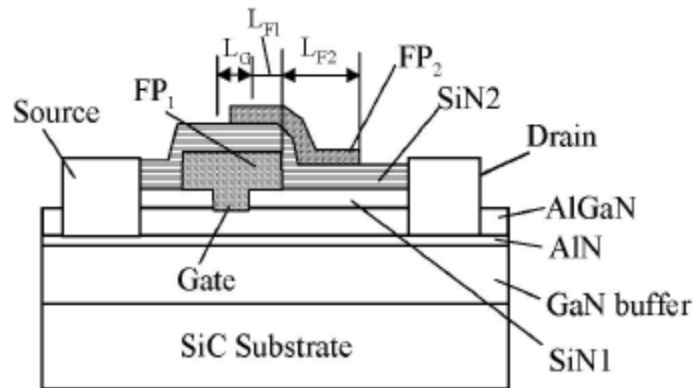


AlGaN/GaN system uniqueness:

- Strong polarization “doping” → high current operation
- High breakdown voltage → high voltage operation
- High saturation velocity → high frequency operation

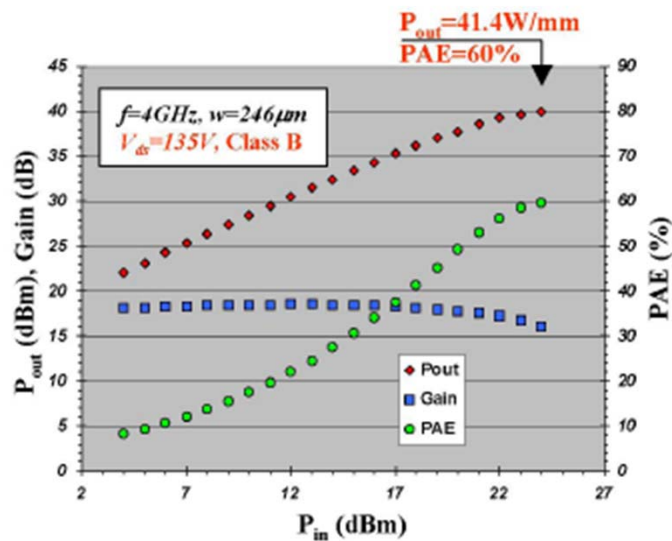
Breakthrough high-f PAs

# Breakthrough RF Power in GaN HEMTs



Micovic, MTT-S 2010

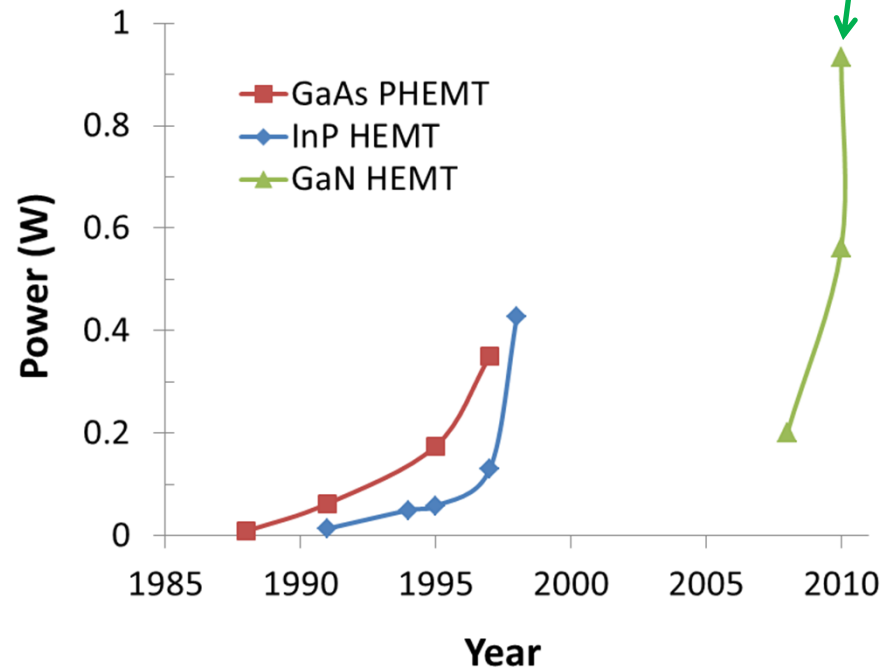
Micovic, Cornell Conf 2010



$P_{out} > 40 \text{ W/mm}$ ,  
over 10X GaAs!

Wu, DRC 2006

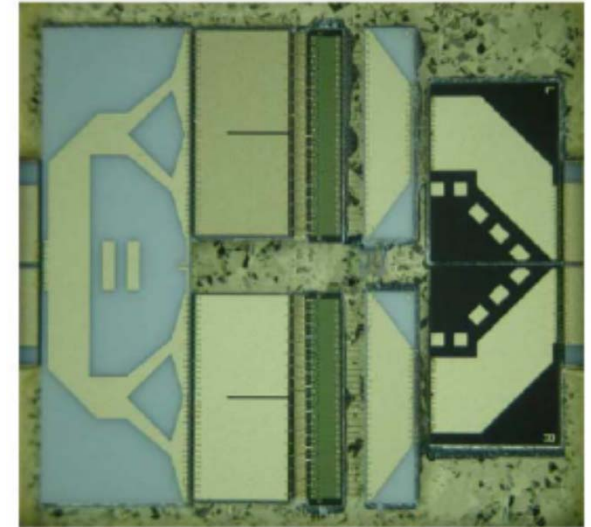
94-95 GHz MMIC PAs:



# GaN HEMT in the field



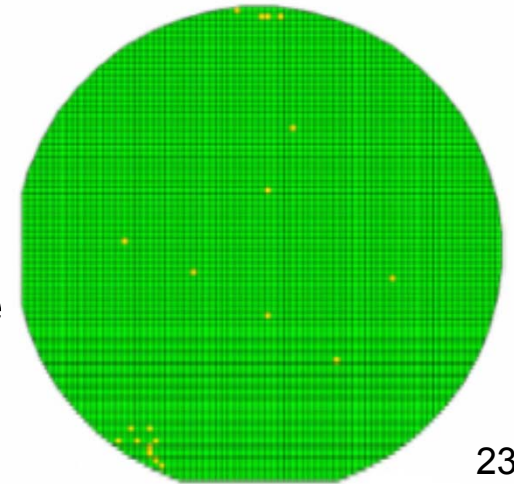
Counter-IED Systems  
(CREW)



200 W GaN HEMT for  
cellular base station  
Kawano, APMC 2005



100 mm GaN-on-SiC volume  
manufacturing  
Palmour, MTT-S 2010

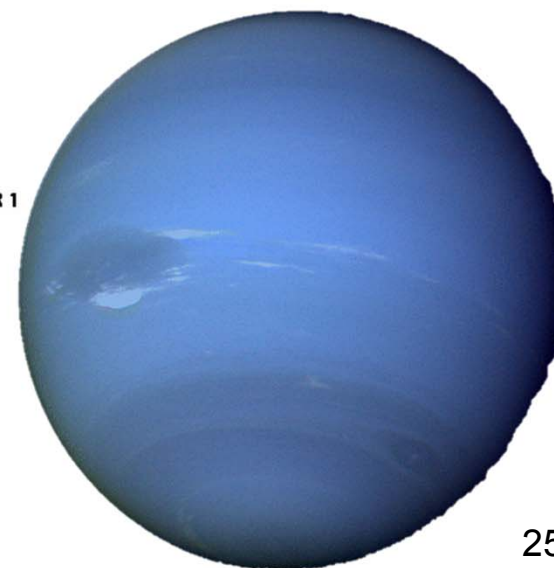
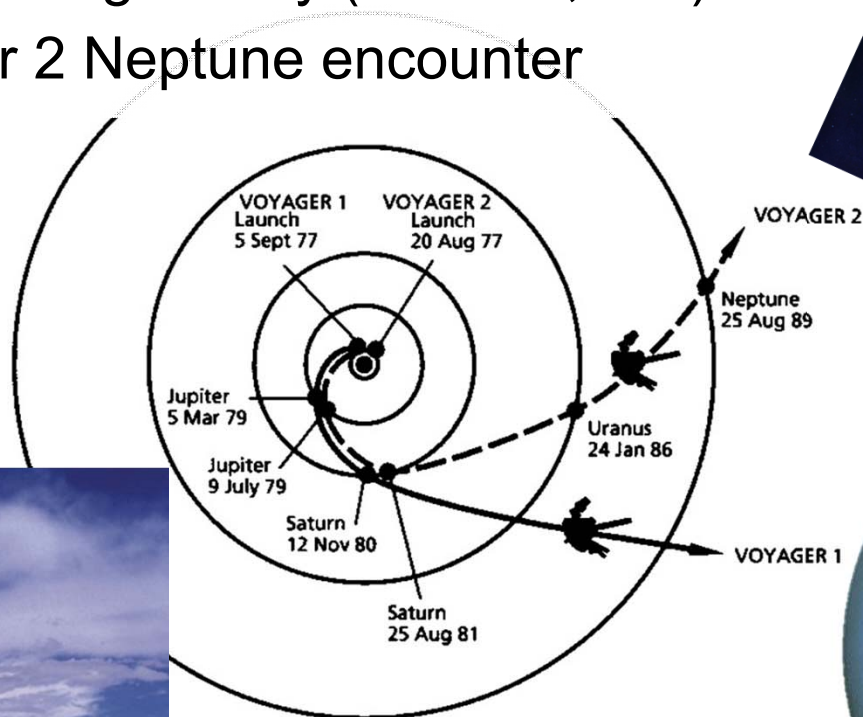
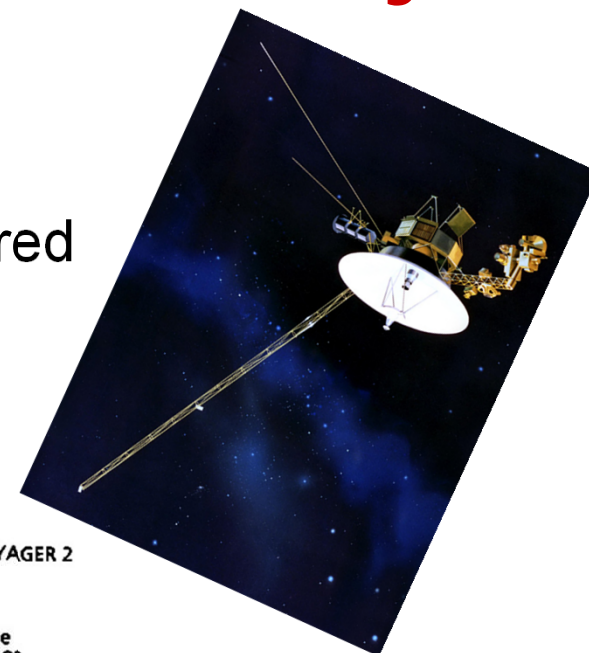


# **Modulation-doped structures in physics**



# Cryogenic HEMTs in radioastronomy

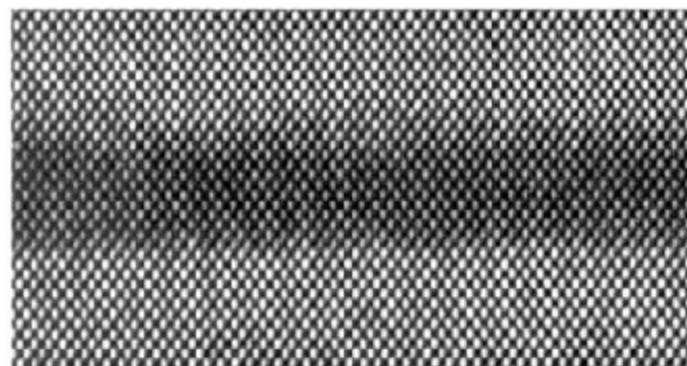
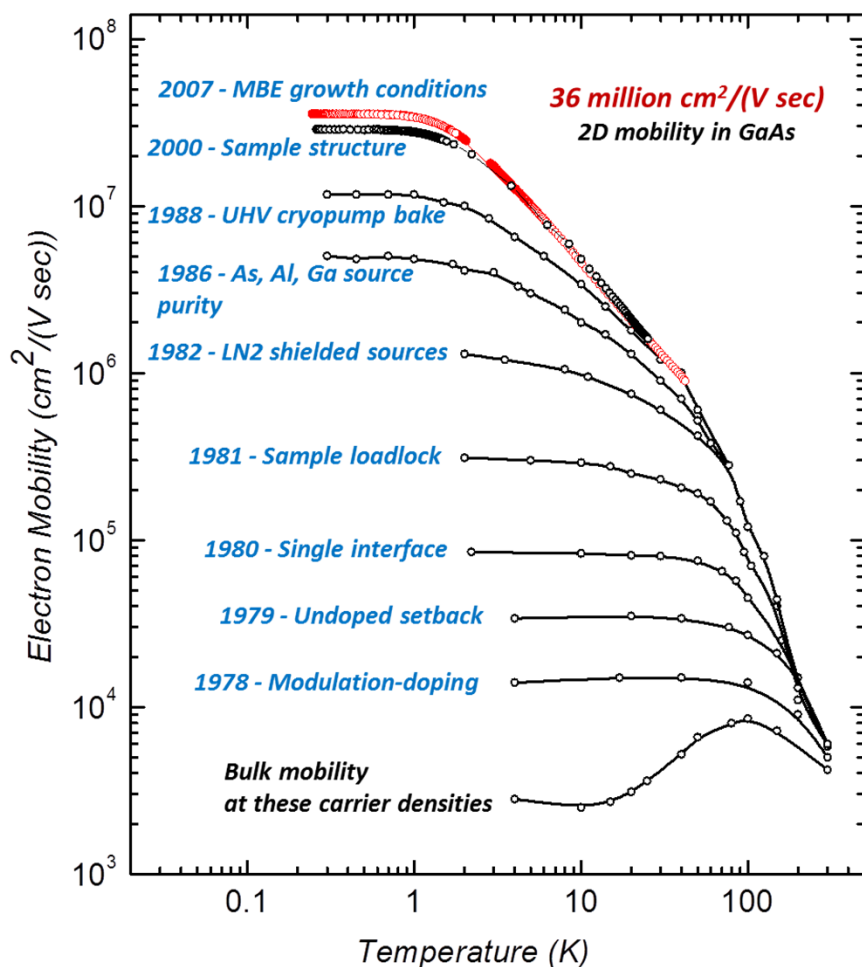
- 1977: launch of Voyager 1 & 2, in mission to four planets
- 1987: AlGaAs/GaAs HEMT amplifiers delivered by GE to Very Large Array (Socorro, NM)
- 1989: Voyager 2 Neptune encounter



Courtesy of Phillip Smith  
(BAE Systems)

# Modulation-doped structures in physics

AlGaAs/GaAs heterostructure: perhaps *the most perfect crystalline interfacial system ever fabricated*



AlAs  
GaAs  
AlAs

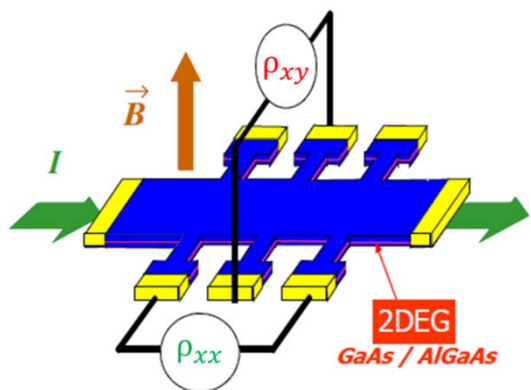
$\mu_e = 3.6 \times 10^7 \text{ cm}^2/\text{V.s}$  at 0.36 K  
( $n_s = 3 \times 10^{11} \text{ cm}^{-2}$ )

Umansky, JCG 2009

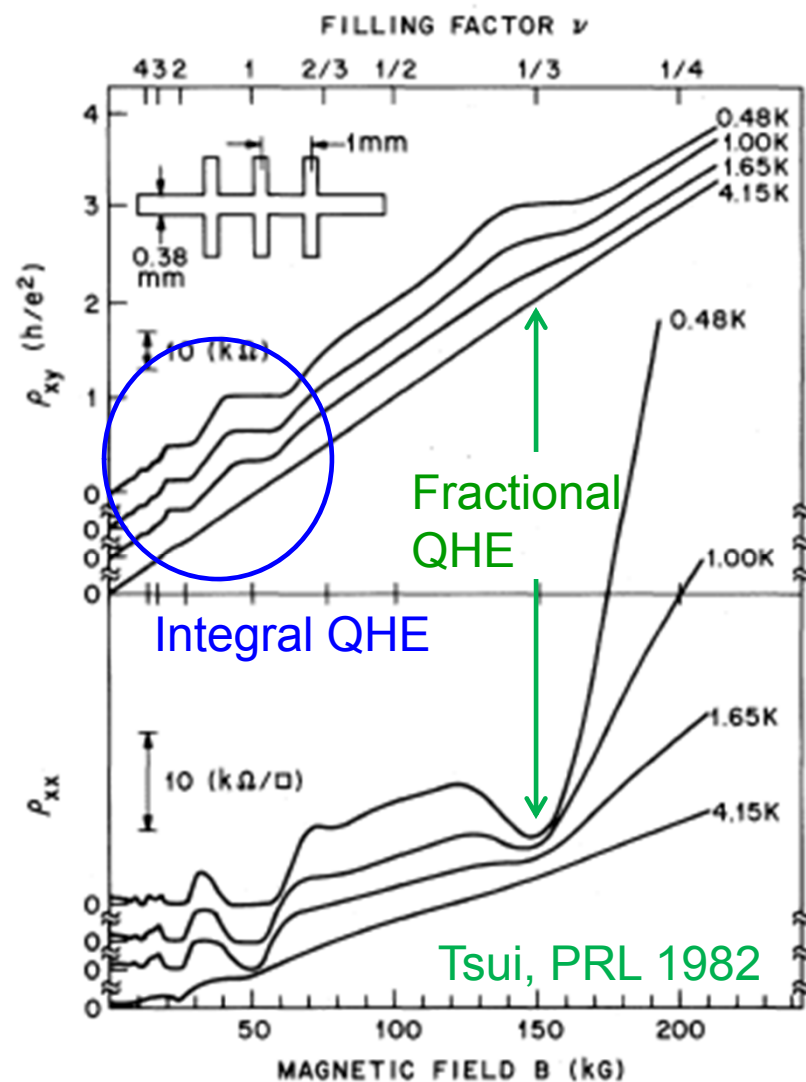
$\mu \uparrow$ : less disorder  
 $\rightarrow$  new physics!

Courtesy of Loren Pfeiffer (Princeton)

# Fractional quantum-Hall effect



$$\rho_{xy} = \frac{h}{ie^2} \text{ index}$$



The Nobel Prize in Physics 1998



Robert B. Laughlin



Horst L. Störmer



Daniel C. Tsui

*“For their discovery of a new form of quantum fluid with fractionally charged excitations”.*

Discovered in sample with  $\mu_e = 9 \times 10^4 \text{ cm}^2/\text{V}\cdot\text{s}$

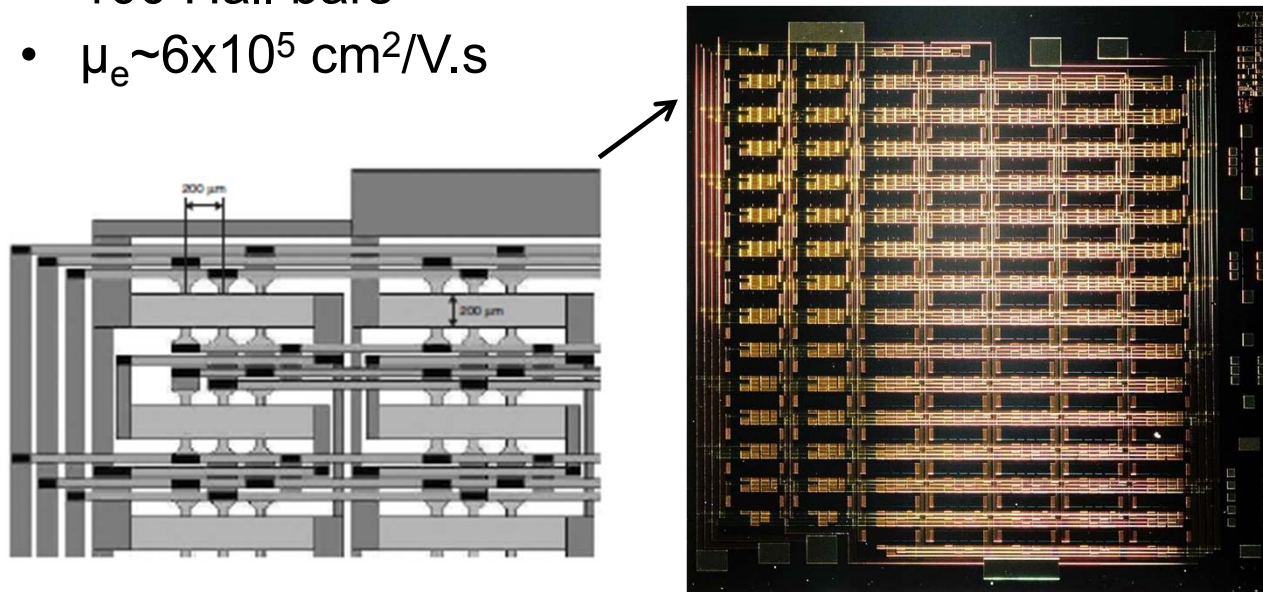
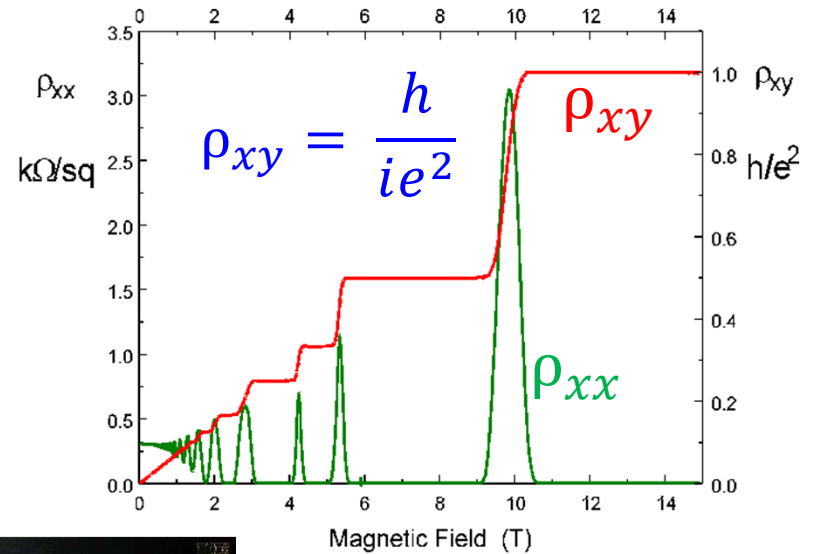


# New international standard for Ohm: AlGaAs/GaAs quantum-Hall bar array

Hall plateaus in Integral QHE determined by fundamental constants  
→ use Hall resistance to define Ohm

## AlGaAs/GaAs quantum-Hall bar array:

- adopted in 1990 as standard for Ohm
- precision: few parts in  $10^9$ !
- 100 Hall bars
- $\mu_e \sim 6 \times 10^5 \text{ cm}^2/\text{V}\cdot\text{s}$



Previous Ohm standard  
(manganin wire):

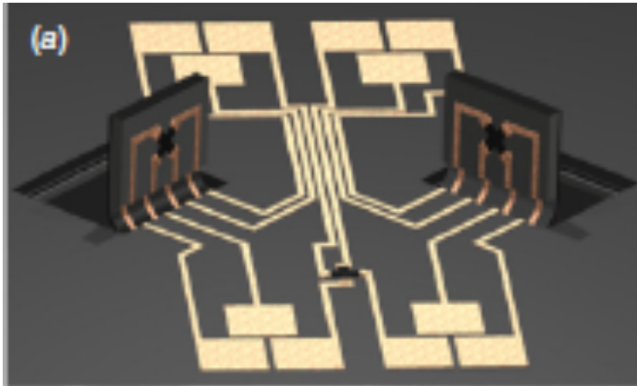


Courtesy of Wilfrid Poirier (Laboratoire National de Métrologie et d'Essais)

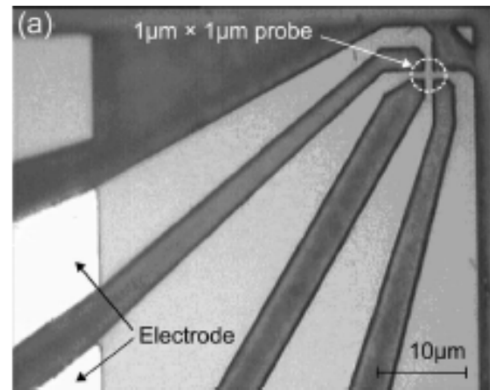


# Future prospects

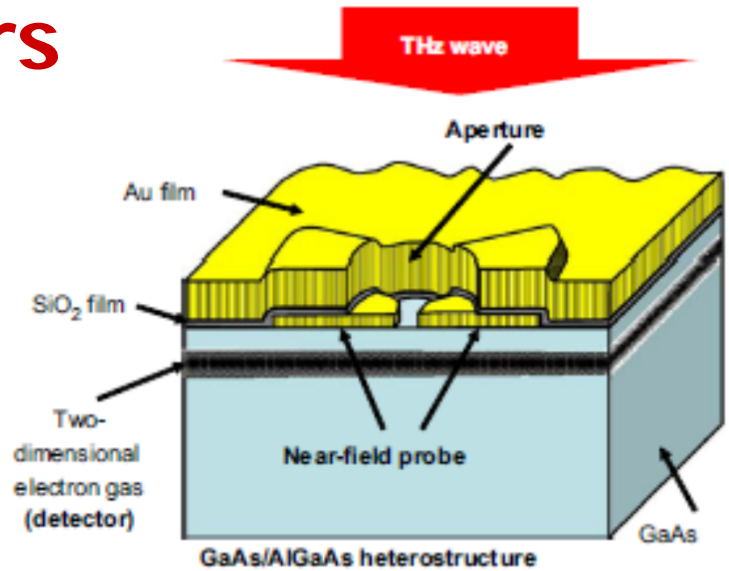
# New sensors



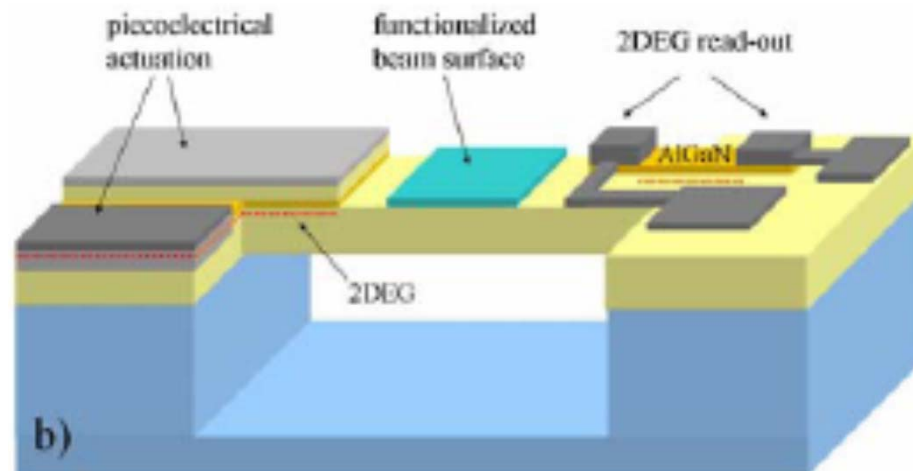
AlGaAs/GaAs 3-axis Hall sensors  
 Todaro JMM 2010



InAlSb/InAsSb Micro-Hall sensors  
 Bando, JAP 2009



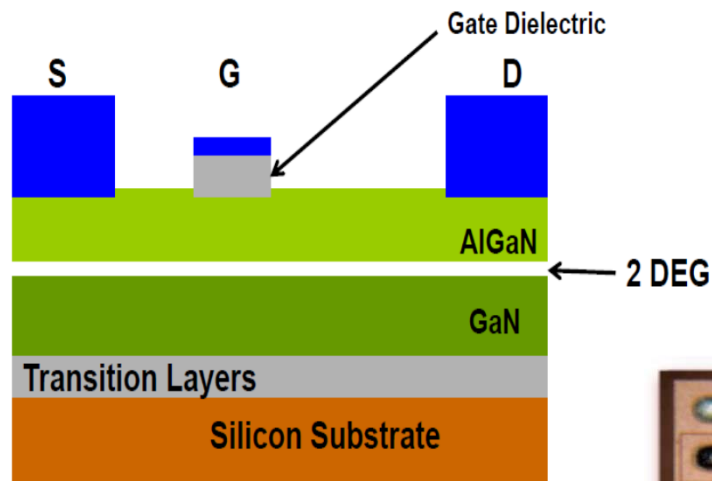
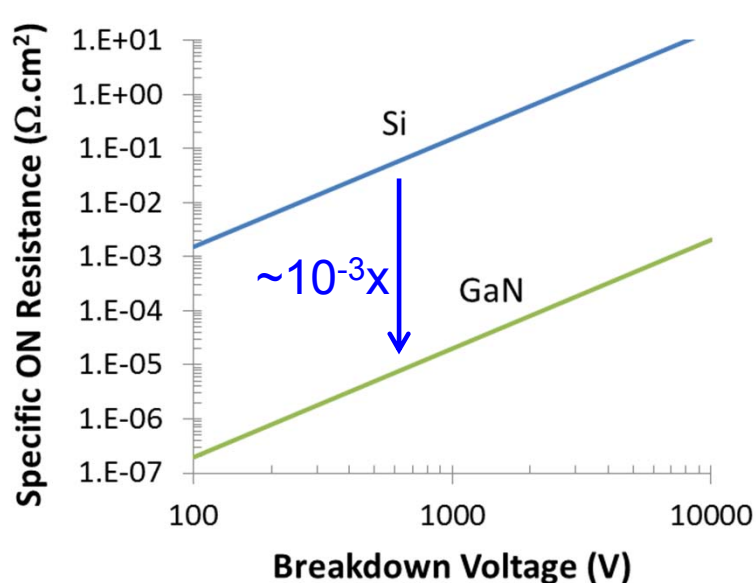
AlGaAs/GaAs THz devices  
 Kawano, Phys E 2010



AlGaN/GaN Bio sensors  
 Niebelschutz, PSSc 2008

# GaN power electronics

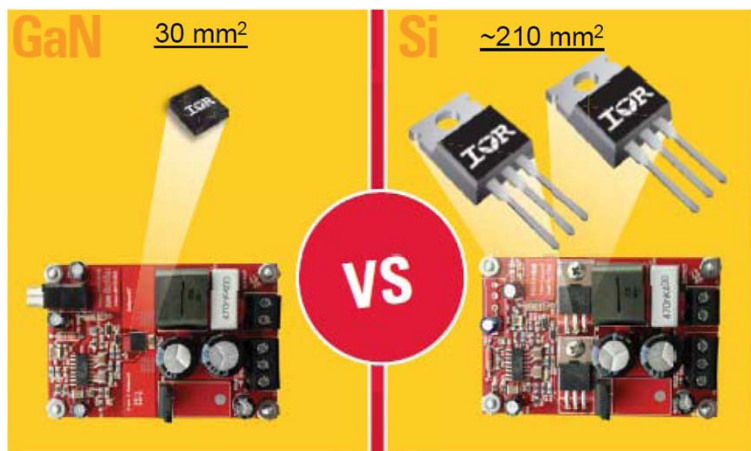
**\$26B  
market in  
2008**



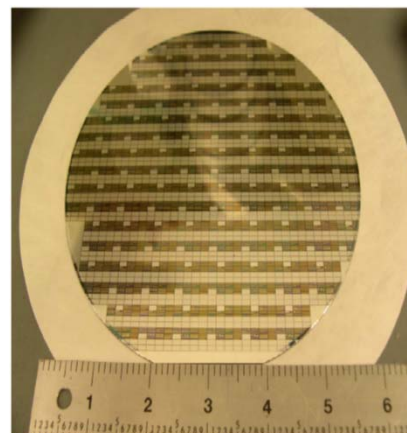
Briere, APEC 2011



GaN enables size shrink:



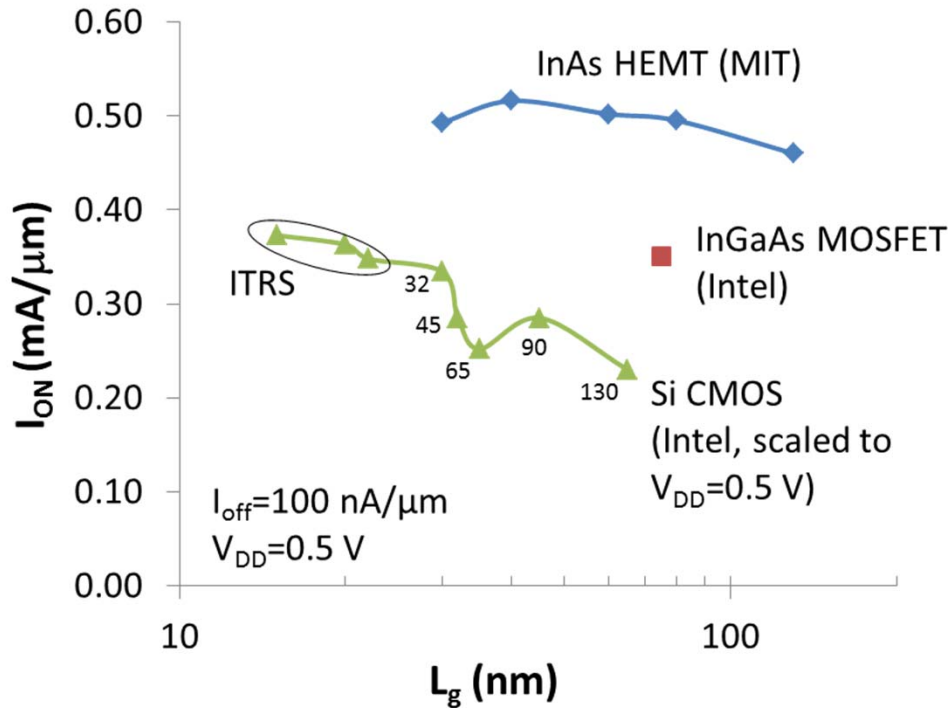
Si-like economics:



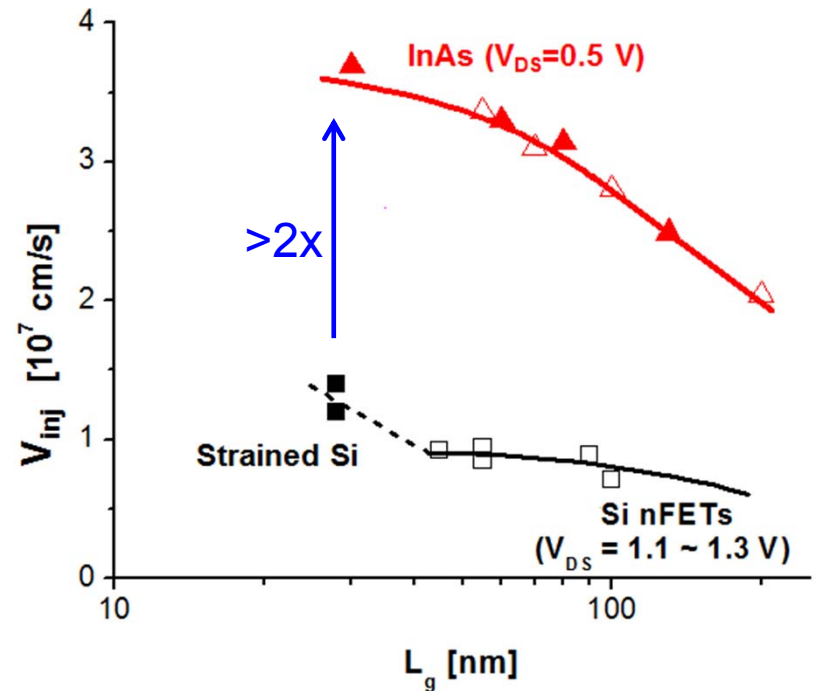
**2-3x  
performance/cost  
advantage over Si**

# III-V CMOS

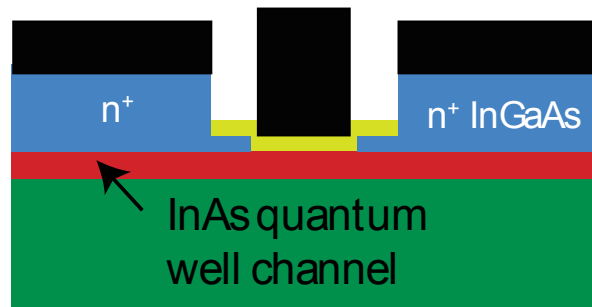
III-V FETs exceed logic performance of Si at 0.5 V



$v_{inj}$  in InGaAs >2x higher than Si at half the voltage



del Alamo, IPRM 2011



Kim, IEDM 2009

**\$110B market in 2010!**

# Epilogue:

## Kroemer's Lemma of New Technology

“The principal applications of any sufficiently new and innovative technology have always been – and will continue to be – applications *created* by that technology.”

Kroemer, Rev Mod Phys 2000

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